Solid State Phenomena Vol. 195 (2013) pp 185-190
© (2013) Trans Tech Publications, Switzerland
doi:10.4028/www.scientific.net/SSP.195.185

Removal of Fine Particle using SAPS Technology and Functional Water

David H. Wang[1, a], Yue Ma[1], Fuping Chen[1], Liangzhi Xie[1], Xi Wang[1], Xiaoyan Zhang[1], Juyoung Lee[2], Dongjoo Kim[2], Jeongyun Lee[2], Pyo Leem[2], and Geunmin Choi[2]

[1] ACM Research (Shanghai), Inc.

[2] Hynix Semiconductor

[a] Email: dwang@acmrcsh.com

Keywords: Particle removal, Functional water, SAPS megasonic technology

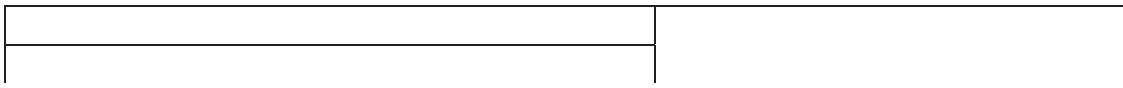
Introduction

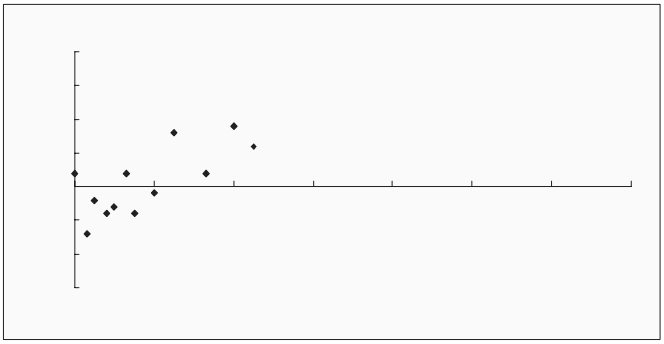
$_2O_2$ in traditional SC1 solution.

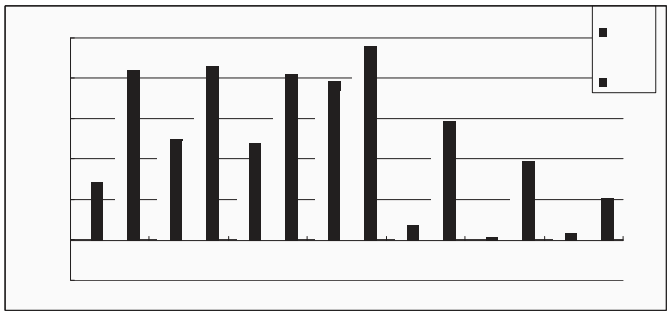
In this paper, the method o acsp alternated ph

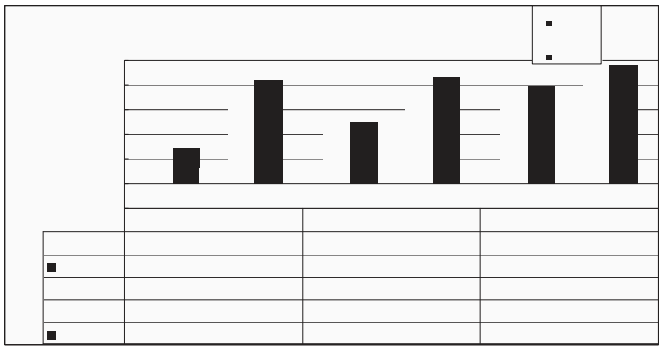
Key Process Parameters Influence on Particle Removal Capability

I



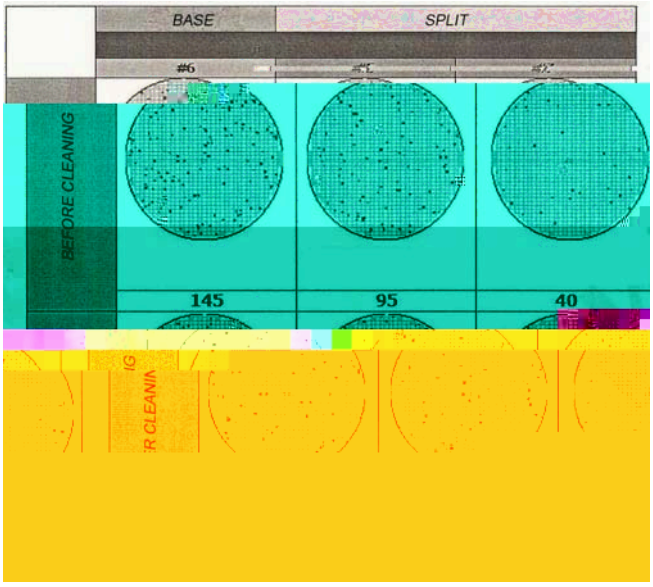






Yield data Validation

III


BASE
SPLIT
#6
BEFORE CLEANING
145
95
40